

Supporting Information:

Stearic Acid as an Atomic Layer Deposition Inhibitor: Spectroscopic Insights from AFM-IR

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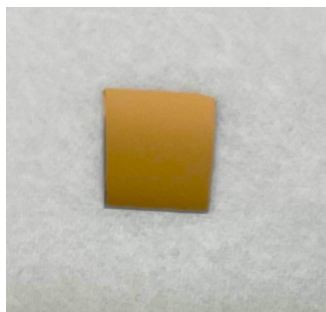
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Plain Copper substrate
after washing with ethanol



Copper substrate after
exposing it to 100°C

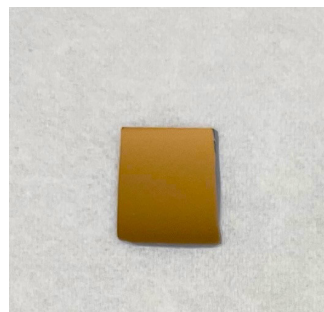


Figure S1. Optical images of bare Cu substrates before (left) and after (right) heating at 100 °C, indicating no visual signs of degradation.

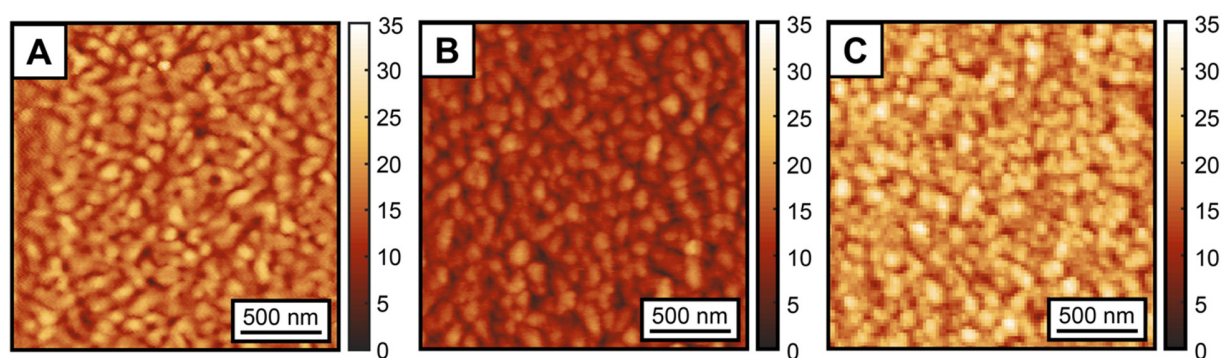


Figure S2. AFM topographs of SA SAMs on Cu after A) 25 cycles, B) 50 cycles and C) 200 cycles of ALD.

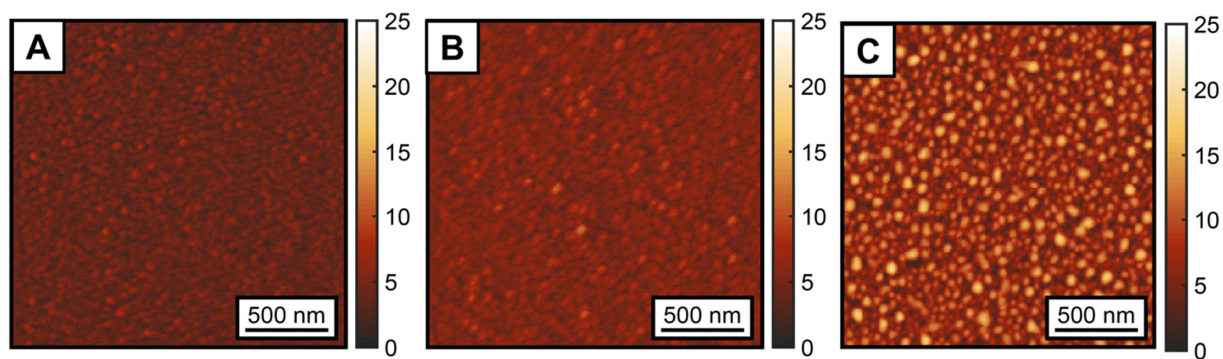


Figure S3. AFM topographs of SA SAMs on Co after A) 25 cycles, B) 50 cycles and C) 200 cycles of ALD.

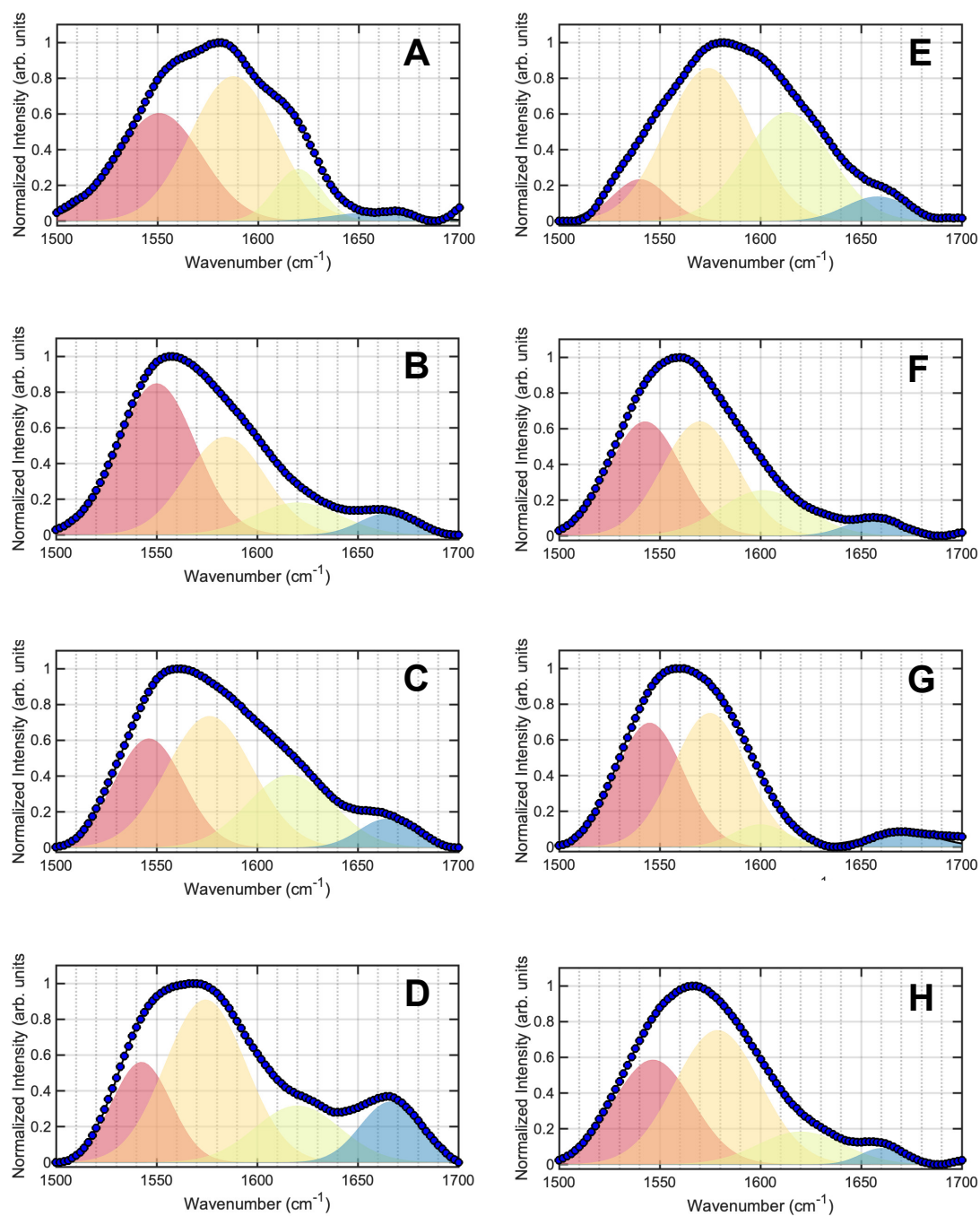


Figure S4. Curve fitting of AFM-IR spectra of SA SAMs corresponding to A) 0 cycles ALD on Cu, B) 25 cycles ALD on Cu, C) 50 cycles ALD on Cu, D) 200 cycles ALD on Cu, E) 0 cycles ALD on Co, F) 25 cycles ALD on Co, G) 50 cycles ALD on Co and H) 200 cycles ALD on Co.